WEST Search History

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DATE: Thursday, February 02, 2006

Hide?	**Set Name**	**Query**	**Hit Count**
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR	
☐	L11	L9 or L10	98
☐	L10	L8 and ($ppm with hydrogen)	25
☐	L9	L8 and terminat$4	81
☐	L8	(rins$3 with hydrogen) and silicon and (megasonic$4 or ultrasonic$4 or vibrat$6)	268
☐	L7	L5 and ((deuterium) with $ppm)	1
☐	L6	L5 and ((hydrogen or deuterium) with $ppm)	12
☐	L5	L4 and wafer	423
☐	L4	(hydrogen or deuterium) and (terminat$4 with surface) and (megasonic or ultrasonic or vibrat$4)	1323
☐	L3	L2 and wafer	1322
☐	L2	L1 and silicon	5182
☐	L1	(hydrogen or deuterium) and terminat$4 and (megasonic or ultrasonic or vibrat$4)	11523

END OF SEARCH HISTORY

WEST Search History

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DATE: Saturday, ~~December 10, 2005~~

Hide?	Set Name	Query	Hit Count
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR	
☐	L26	clean$3 with vibration with terminat$3 with silicon	1
☐	L25	L24 and (Si or silicon) and (110 or 001)	371
☐	L24	(terminat$4 with (hydrogen or deuterium)) and (vibrat$4 or ultrasonic$4)	966
☐	L23	L21 and (terminat$4 with (hydrogen or deuterium))	15
☐	L22	L21 and terminat$4	97
☐	L21	deuterium and ultrasonic and clean$3	218
☐	L20	(terminat$3 with deuterium) and vibrat$	6
☐	L19	(terminate with deuterium) and vibrat$	2
☐	L18	(terminate with deuterium) and clean$3	7
☐	L17	(terminate with deuterium) and (ultrasonic$4 or vibrat$4) and clean$3	2
☐	L16	(terminate with (silicon or hydrogen)) and vibrat$4 and ((heavy adj hydrogen) or deuterium)	8
☐	L15	(RCA with (SC-1 or SC1)) same (reduc$5 with OH)	7
☐	L14	(orient$5 with (100 or 001 or 110)) and (DHF with clean$3)	8
☐	L13	L12 and (DHF with clean$3)	86
☐	L12	L11 and (DHF with surface)	153
☐	L11	DHF and ((wafer or silicon or substrate) with (100 or 001 or 110))	550
☐	L10	L9 and (110 or 100 or 001)	71
☐	L9	(clean$3 with solution with HF with DI)	86
☐	L8	L7 and (HF with solution with DI)	97
☐	L7	((100 or 110) with (silicon or wafer or substrate)) and clean$3 and (HF with DI)	211
☐	L6	((100 or 110) with (silicon or wafer or substrate)) and clean$3 and (HF with (dissolved adj oxygen))	8
☐	L5	(clean$3 with (wafer or substrate) with HF with dissolved with oxygen)	2
☐	L4	HF same clean$3 same (dissolved adj oxygen)	21
☐	L3	L2 and HF	39
☐	L2	L1 and ((dissolved with oxygen) with (ppm or ppb))	81
☐	L1	(semiconductor adj (wafer or substrate)) and ((wafer or substrate) same clean$3)	38694

END OF SEARCH HISTORY